

Abstract

Defect Repair Method, In Particular For Repairing Quartz Defects On Alternating Phase Shift Masks

The invention relates to a defect repair method, in particular for repairing quartz defects on alternating phase shift masks, wherein, for repairing defects (5) existing on one and the same component (1), both, defect repair method steps substantially based on mechanical processes (S3), in particular nanomachining method steps, and defect repair method steps substantially based on etching processes (S2), in particular FIB (Focused Ion Beam) method steps, are used. Moreover, the invention relates to a component (1), in particular a photomask, repaired by making use of such a defect repair method.